

Applicant(s): Isamu Kobori et al.

METHOD OF MANUFACTURING A SEMICONDUCTOR
METHOD OF MANUFACTURING A THIN-FILM TRANSISTOR
AND THIN-FILM TRANSISTOR

Fig. 1

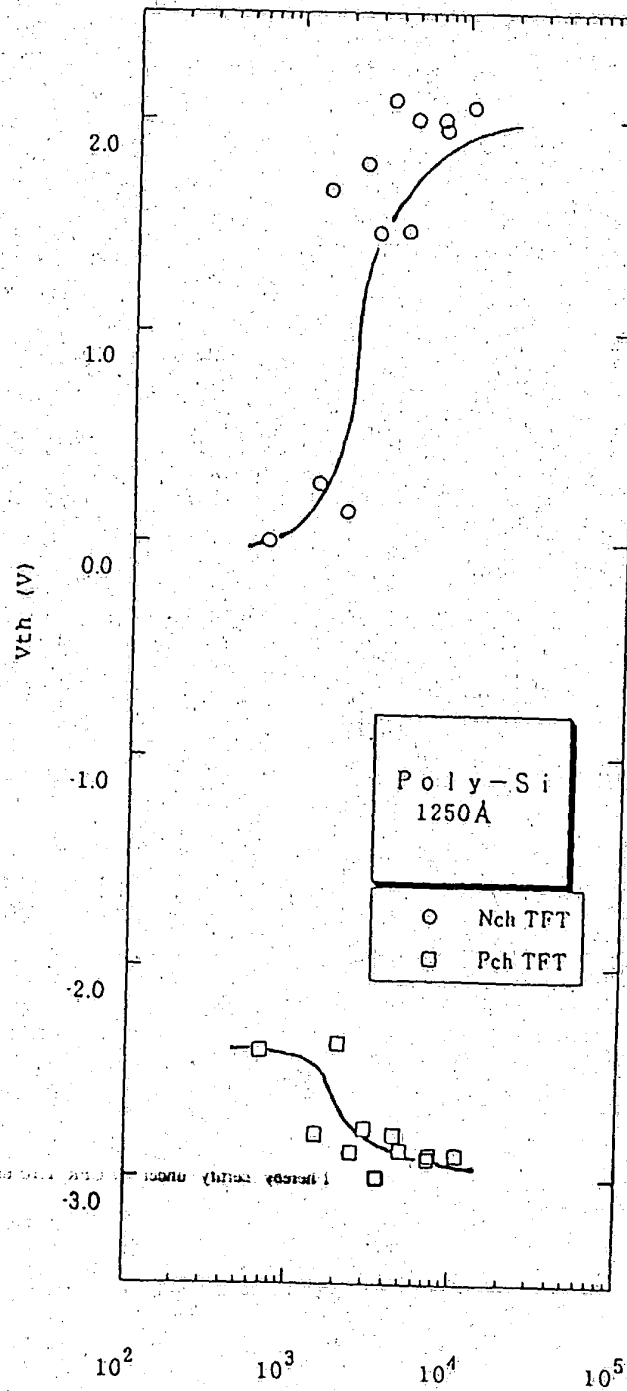
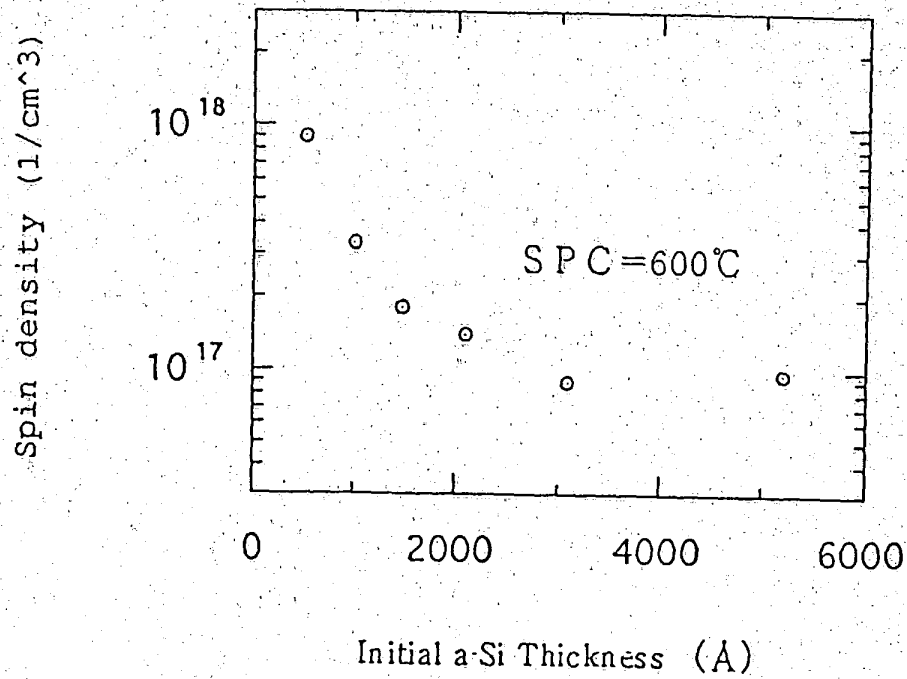
AREA OF ISLAND-LIKE (μm^2)
REGION

Fig. 2



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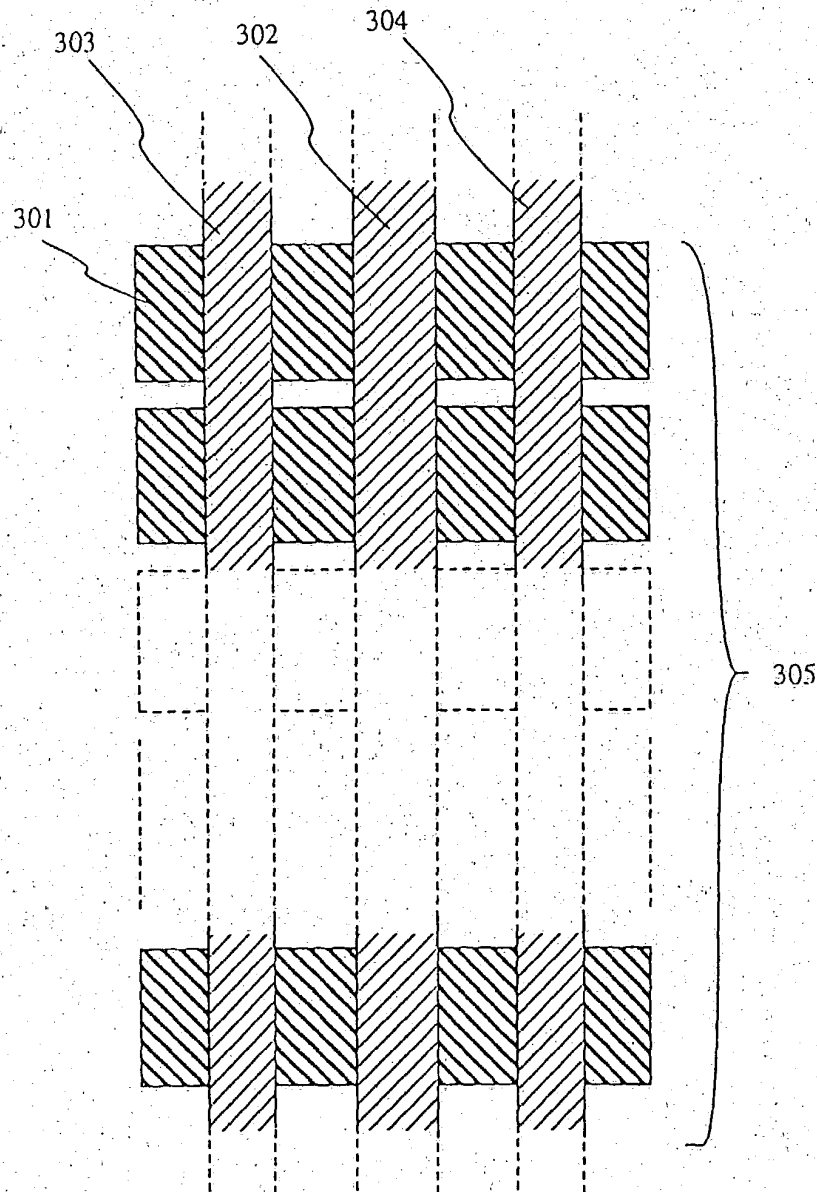
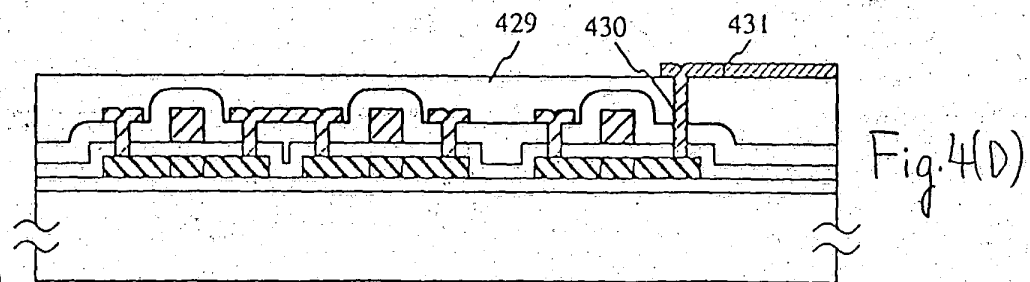
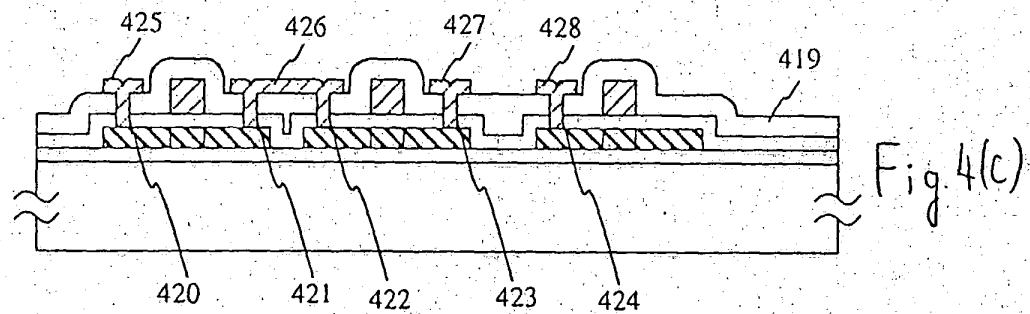
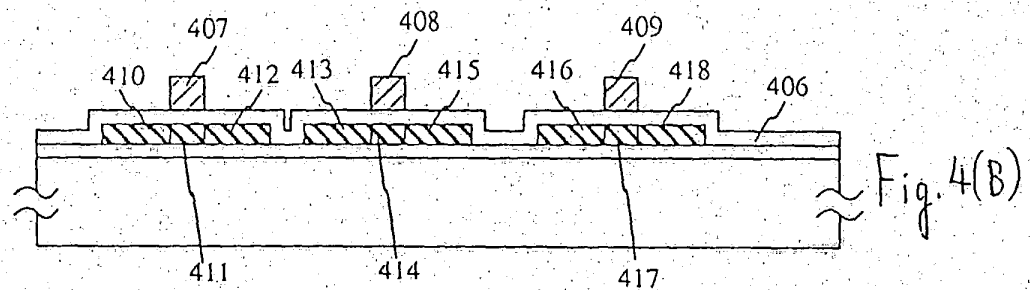
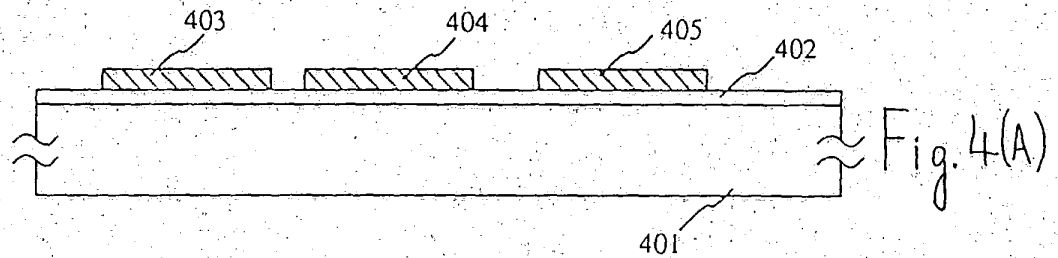


Fig. 3



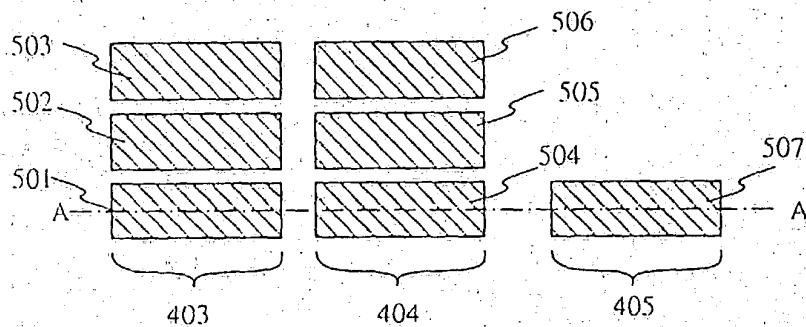


Fig. 5(A)

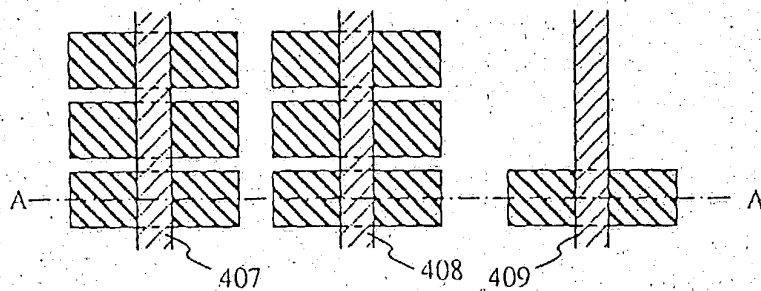


Fig. 5(B)

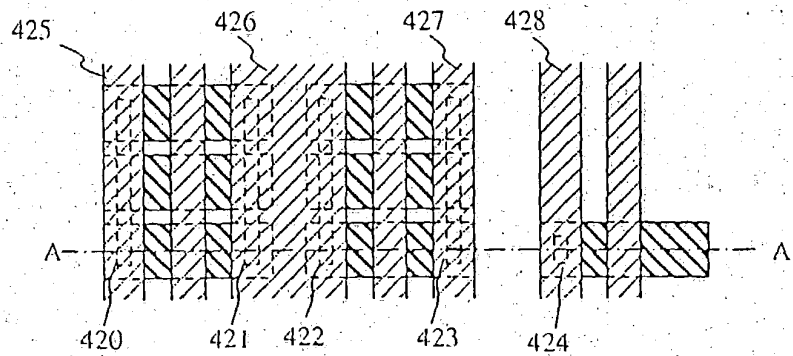


Fig. 5(c)

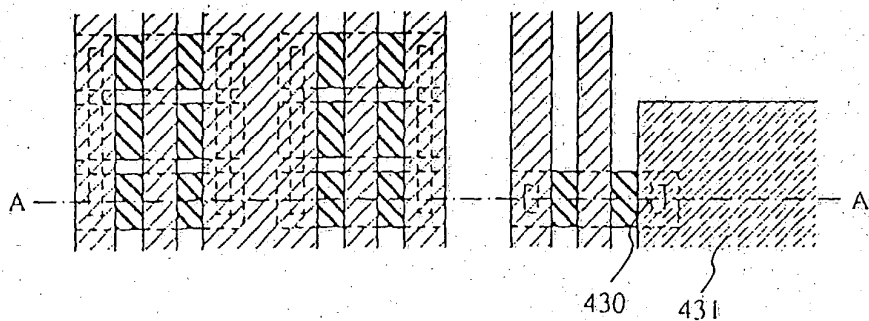


Fig. 5(D)